Cymer Delivers Second Generation Solution for Reduction of Neon Consumption on ArF Light Sources

Neon reduction program reduces chipmaker costs

San Diego, California, December 14, 2015 – Cymer, an industry leader in developing lithography light sources used by chipmakers to pattern advanced semiconductor chips, announced the availability of its second generation solution to reduce the consumption of neon gas in ArF light sources. Neon is used in the routine operation of semiconductor light sources, and has recently been subject to supply limitations. Cymer’s latest gas control technology is expected to deliver up to 75% reduction in neon consumption, further reducing the impact on chipmakers from neon shortages and price fluctuations.

This is the result of the comprehensive Neon Reduction Program started by Cymer earlier this year that led to a solution to reduce neon consumption by approximately 50% for ArF and 30% for KrF released in September which was adopted widely by customers. The Program consisted of multiple elements:

- Providing chipmakers with short-term containment solutions to immediately reduce neon consumption
- Expanding the approved list of gas suppliers through a rapid qualification process
- Developing new gas control technology that would fundamentally reduce the gas consumption while maintaining light source throughput and availability
- Implementing a longer-term reclaim and recycling program to reduce demand for neon

“Neon supply continuity and price variability have strongly impacted our customers,” said David Knowles, Vice President of Cymer Light Source. “This latest release is part of our commitment to reduce the dependence on neon by collaborating with our customers to quickly release new solutions.”
In addition to the neon reduction solutions, Cymer continues to support efforts to capture and reclaim the used neon gas from light sources. Cymer is also developing a gas recycling unit that can be installed in a semiconductor fab to provide local recycling through a sequence of filtering and reconstituting the correct mixture for reuse.

“The rapid onset of the neon supply issue, and the potential ramifications—including a potential disruption in integrated circuit (IC) production—made a timely resolution critical,” said Ted Cacouris, Product Marketing Director at Cymer. “We believe that the Neon Reduction Program has eased supply constraints and produced neon-saving solutions for the semiconductor industry that will amount to over 70 million liters per year, or more than $200M.”

About Cymer
Cymer, an ASML company, is an industry leader in developing lithography light sources, used by chipmakers worldwide to pattern advanced semiconductor chips. Cymer’s light sources, and ongoing innovations, are available to all semiconductor and semiconductor equipment companies to enable advanced device manufacturing today and into the future. Cymer is pioneering the industry’s transition to EUV light source technology, the next viable step on the technology roadmap for the creation of smaller, faster and more energy-efficient chips. The company is headquartered in San Diego, California. www.cymer.com

Cautionary Statement Regarding Forward-Looking Statements
This document contains statements that are forward-looking, including statements with respect to Cymer’s neon gas reduction program, including reduced neon consumption and accompanying cost reductions that chipmakers can achieve using the Cymer solution, the effects of the program including a reduction in neon supply constraints and effectiveness of neon recycling. Forward-looking statements do not guarantee future performance and involve risks and uncertainties. Actual results may differ materially from projected results as a result of certain risks and uncertainties. These risks and uncertainties include the risk that Cymer’s neon gas reduction program does not reduce neon consumption by chipmakers or their dependence on neon or insulate customers from fluctuations of neon supply and other risks indicated in the risk factors included in ASML’s Annual Report on Form 20-F and other filings with the US Securities and Exchange Commission. These forward-looking statements are made only as of the date of this document. ASML does not undertake to update or revise the forward-looking statements, whether as a result of new information, future events or otherwise.